| Updated Search Results Case No. 10/087,601   |                    |
|--|--------------------|
| (object adj area) and (image adj area)   | USPAT; US-PGPUB;   |
| ,  | EPO; JPO; DERWENT; |
|  | IBM_TDB            |
| (((object adj area) and (image adj area)) and                                      | USPAT; US-PGPUB;   |
| (focusing adj lens\$2)) and (deflect\$4 adj lens\$2)                               | EPO; JPO; DERWENT; |
| ((************************************   | IBM TDB            |
| ((object adj area) and (image adj area)) and                                       | USPAT; US-PGPUB;   |
| (focusing adj lens\$2)   | EPO; JPO; DERWENT; |
| (10000mg day 1011042)  | IBM TDB            |
| (((object adj area) and (image adj area)) and                                      | USPAT; US-PGPUB;   |
| (focusing adj lens\$2)) and deflect\$4   | EPO; JPO; DERWENT; |
| (100doing dd) 1011dw2// dild delieotw4   | IBM TDB            |
| focus\$3 with lens\$2 with first   | USPAT; US-PGPUB;   |
| With lensus with hist  | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| (first adj focus\$3 adj lens) and (second adj focus\$3                             |                    |
| adj lens)  | EPO; JPO; DERWENT; |
| adjiciis)  | IBM TDB            |
| (359/619,622,637,558).CCLS.  | USPAT; US-PGPUB;   |
| (339/019,022,037,030/.00E3.  | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| (430/5,22,30,322,296).CCLS.  | USPAT; US-PGPUB;   |
| (450/5,22,50,522,230). GGLG.   | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| (250/492.22,492.1).CCLS.   | USPAT; US-PGPUB;   |
| (200/492.22,432.1).0010.   | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| (702/126,40).CCLS.   | USPAT; US-PGPUB;   |
| ((102) 120,40).0020.   | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| (204/157.68,456).CCLS.   | USPAT: US-PGPUB:   |
| (2047107:00,400):00E0:   | EPO; JPO; DERWENT; |
|  | IBM TDB            |
| ((359/619,622,637,558).CCLS.) or   | USPAT; US-PGPUB;   |
| ((430/5,22,30,322,296).CCLS.) or   | EPO; JPO; DERWENT; |
| ((250/492.22,492.1).CCLS.) or  | IBM TDB            |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)                                   |                    |
| ((102/120,40).0020.) 01 ((204/101.00,400).0020.)                                   |                    |
| (((359/619,622,637,558).CCLS.) or  | USPAT; US-PGPUB;   |
| (((30/5,22,30,322,296).CCLS.) or   | EPO; JPO; DERWENT; |
| ((250/492.22,492.1).CCLS.) or  | IBM TDB            |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))                                  | l <b>=</b>         |
| and (electron\$1 with (project\$4 or imag\$3))                                     |                    |
|  |                    |
| (((359/619,622,637,558).CCLS.) or  | USPAT; US-PGPUB;   |
| (((430/5,22,30,322,296).CCLS.) or  | EPO; JPO; DERWENT; |
| ((450/5,22,35,322,250).00L0.) or   | IBM TDB            |
| ((250/492.22,492.1).CCLS.) or<br>((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) |                    |
| and (electron\$1 with beam\$1 with (project\$4 or                                  |                    |
| imag\$3))  |                    |
| ппауфо//   | <u> </u>           |

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| ((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron\$1 with beam\$1 with (project\$4 or imag\$3 or deflect\$4)) (((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable)) | USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB<br>USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB |
|---|--|
| ((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and (focus\$3 with lens\$2)   | USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB  |
| ((((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and (focus\$3 with lens\$2)) and object\$1 and image\$1   | USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB  |
| ((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 with lens\$2) with (two or (first and second)))  | USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB  |
| (((((359/619,622,637,558).CCLS.) or<br>((430/5,22,30,322,296).CCLS.) or<br>((250/492.22,492.1).CCLS.) or<br>((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))<br>and ((electron\$1 or particle\$1) with beam\$1 with<br>(project\$4 or imag\$3 or deflect\$4 or variable))) and<br>((focus\$3 with lens\$2) same first same second)   | USPAT; US-PGPUB;<br>EPO; JPO; DERWENT;<br>IBM_TDB  |

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| (((((359/619,622,637,558).CCLS.) or                     | USPAT; US-PGPUB;                |
|---|---------------------------------|
|   |                                 |
| ((430/5,22,30,322,296).CCLS.) or                        | EPO; JPO; DERWENT;  <br>IBM_TDB |
| ((250/492.22,492.1).CCLS.) or                           | IBINITI DB                      |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))       |                                 |
| and ((electron\$1 or particle\$1) with beam\$1 with     |                                 |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and |                                 |
| ((focus\$3 with lens\$2) with two)                      |                                 |
| (((((359/619,622,637,558).CCLS.) or                     | USPAT; US-PGPUB;                |
| ((430/5,22,30,322,296).CCLS.) or                        | EPO; JPO; DERWENT;              |
| ((250/492.22,492.1).CCLS.) or                           | IBM TDB                         |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))       | _                               |
| and ((electron\$1 or particle\$1) with beam\$1 with     |                                 |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and |                                 |
| ((focus\$3 adj lens\$2) with two)                       |                                 |
|   |                                 |
| (((((359/619,622,637,558).CCLS.) or                     | USPAT; US-PGPUB;                |
| ((430/5,22,30,322,296).CCLS.) or                        | EPO; JPO; DERWENT;              |
| ((250/492.22,492.1).CCLS.) or                           | IBM_TDB                         |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))       |                                 |
| and ((electron\$1 or particle\$1) with beam\$1 with     |                                 |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and |                                 |
| ((focus\$3 adj lens\$2) with two)                       |                                 |
|   |                                 |
| (((((359/619,622,637,558).CCLS.) or                     | USPAT; US-PGPUB;                |
| ((430/5,22,30,322,296).CCLS.) or                        | EPO; JPO; DERWENT;              |
| ((250/492.22,492.1).CCLS.) or                           | IBM_TDB                         |
| ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))       |                                 |
| and ((electron\$1 or particle\$1) with beam\$1 with     |                                 |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and | 1                               |
| ((focus\$3 adj lens\$2) with second)                    |                                 |
| (359/283).CCLS.   | USPAT; US-PGPUB;                |
| [(003/203).00E0.  | EPO; JPO; DERWENT;              |
|   | IBM_TDB                         |
| ((359/283).CCLS.) and ((electron\$1 or particle\$1)     | USPAT; US-PGPUB;                |
| with beam\$1 with (project\$4 or imag\$3 or deflect\$4  | EPO; JPO; DERWENT;              |
| or variable))   | IBM TDB                         |
| ((359/283).CCLS.) and ((electron\$1 or particle\$1)     | USPAT; US-PGPUB;                |
| with (project\$4 or imag\$3 or deflect\$4 or variable)) | EPO; JPO; DERWENT;              |
| (with (projector of imagos of deflector of variable))   | IBM TDB                         |
| ((359/619,622,637,558).CCLS.) or                        | USPAT; US-PGPUB;                |
| ((359/283).CCLS.)                                       | EPO; JPO; DERWENT;              |
| ((333.233).3323.)                                       | IBM_TDB                         |
| (((((359/619,622,637,558).CCLS.) or                     | USPAT; US-PGPUB;                |
| ((359/283) CCLS.)) and ((electron\$1 or particle\$1)    | EPO; JPO; DERWENT;              |
| with beam\$1 with (project\$4 or imag\$3 or deflect\$4  | IBM_TDB                         |
| or variable))) and ((focus\$3 adj lens\$2) with two)    | -                               |
|   |                                 |
|   |                                 |

| (((((359/619,622,637,558).CCLS.) or  | USPAT; US-PGPUB;   |
|--|--------------------|
| (((359/283).CCLS.)) and ((electron\$1 or particle\$1)  | EPO; JPO; DERWENT; |
| with beam\$1 with (project\$4 or imag\$3 or deflect\$4   | IBM_TDB            |
| or variable))) and ((focus\$3 adj lens\$2) with  | I BIVI_1 DB        |
| (second)   |                    |
| (((359/619,622,637,558).CCLS.) or  | USPAT; US-PGPUB;   |
| (((359/283).CCLS.)) and ((electron\$1 or particle\$1)  | EPO; JPO; DERWENT; |
| with beam\$1 with (project\$4 or imag\$3 or deflect\$4   | IBM_TDB            |
| or variable))  | 10W_100            |
| ((electron\$1 or particle\$1) with beam\$1 with  | USPAT; US-PGPUB;   |
| ((election of particles i) with bearing i with<br>(project\$4 or imag\$3 or deflect\$4 or variable))     | EPO; JPO; DERWENT; |
| (projective or imagino or deflective or variable))   | IBM TDB            |
| ("5260151").PN.  | USPAT              |
| ( 5200131 ).FN.<br>("5376505").PN.   | USPAT              |
| (*5079112").PN.  | USPAT              |
| ("5316879").PN.  | USPAT              |
| ("5130213").PN.  |                    |
|  | USPAT              |
| ("5258246").PN.  | USPAT US BORUE     |
| scalpel  | USPAT; US-PGPUB;   |
|  | EPO; JPO; DERWENT; |
| (1) (1) (1) (1) (1) (1) (1) (1) (1) (1)  | IBM_TDB            |
| scalpel and (focus\$3 with lens\$2)  | USPAT; US-PGPUB;   |
|  | EPO; JPO; DERWENT; |
|  | IBM_TDB            |
| scalpel and ((electron\$1 or particle\$1) with   | USPAT; US-PGPUB;   |
| (project\$4 or imag\$3 or deflect\$4 or variable))   | EPO; JPO; DERWENT; |
|  | IBM_TDB            |
| (scalpel and (focus\$3 with lens\$2)) and (scalpel   | USPAT; US-PGPUB;   |
| and ((electron\$1 or particle\$1) with (project\$4 or  | EPO; JPO; DERWENT; |
| imag\$3 or deflect\$4 or variable)))   | IBM_TDB            |
| (scalpel and ((electron\$1 or particle\$1) with  | USPAT; US-PGPUB;   |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and  | EPO; JPO; DERWENT; |
| ((focus\$3 with lens\$2) same first same second)   | IBM_TDB            |
| (scalpel and ((electron\$1 or particle\$1) with  | USPAT; US-PGPUB;   |
| ((project\$4 or imag\$3 or deflect\$4 or variable))) and   | EPO; JPO; DERWENT; |
| ((focus\$3 with lens\$2) with two)   | IBM TDB            |
| ((scalpel and ((electron\$1 or particle\$1) with   | USPAT; US-PGPUB;   |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and  | EPO; JPO; DERWENT; |
| ((focus\$3 with lens\$2) same first same second)) or   |                    |
| (((scalpel and ((electron\$1 or particle\$1) with  | 10.11_100          |
| ((scalper and ((electrons)) or particles () with (project\$4 or imag\$3 or deflect\$4 or variable))) and |                    |
| ((focus\$3 with lens\$2) with two))  |                    |
| ((1000545 WILLI TELISAZ) WILLI TWO))   |                    |
| (((scalpel and ((electron\$1 or particle\$1) with  | USPAT; US-PGPUB;   |
| 1,,,   | EPO; JPO; DERWENT; |
| (project\$4 or imag\$3 or deflect\$4 or variable))) and  |                    |
| ((focus\$3 with lens\$2) same first same second) ) or  | מטו _ועוטון        |
| (((scalpel and ((electron\$1 or particle\$1) with  |                    |
| ((project\$4 or imag\$3 or deflect\$4 or variable))) and   |                    |
| ((focus\$3 with lens\$2) with two) )) and deflect\$4   |                    |
|  | L                  |

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## Search Results Case No. 10/087,601

| Search Results | <u> </u> | 7. 10/00//,001   |            |
|----------------|----------|--|------------|
| US 6280906 B1  | USPAT    | Method of imaging a mask pattern on a substrate by means of EUV radiation, and | 430/296    |
|                |          | apparatus and mask for performing the  |            |
|                |          | method   |            |
| US 6355384 B1  | USPAT    | Mask, its method of formation, and a   | 430/5      |
|                | 1        | semiconductor device made thereby  |            |
| US 6090527 A   | USPAT    | Electron beam exposure mask and method   | 430/296    |
|                |          | of manufacturing the same and electron   |            |
|                |          | beam exposure method   |            |
| US 5520297 A   | USPAT    | Aperture plate and a method of   | 216/12     |
|                |          | manufacturing the same   |            |
| US 5849437 A   | USPAT    | Electron beam exposure mask and method   | 430/5      |
| 1              |          | of manufacturing the same and electron   |            |
|                |          | beam exposure method   |            |
| US 6326629 B1  | USPAT    | Projection lithography device utilizing  | 250/492.2  |
|                |          | charged particles  |            |
| US 6171736 B1  | USPAT    | Projection-microlithography alignment  | 430/22     |
|                |          | method utilizing mask with separate mask                                       |            |
|                |          | substrates   |            |
| US 6180289 B1  | USPAT    | Projection-microlithography mask with  | 430/5      |
|                |          | separate mask substrates   |            |
| US 6124596 A   | USPAT    | Charged-particle-beam projection apparatus                                     | 250/396ML  |
|                |          | and transfer methods   | 040404.05  |
| US 5466904 A   | JUSPAT   | Electron beam lithography system   | 219/121.25 |
|                |          |  | 050/400 00 |
| US 5973333 A   | JUSPAT   | Charged-particle-beam pattern-transfer   | 250/492.23 |
|                | L        | apparatus and methods  |            |